



TotalEnergies

Refining & Chemicals
Polymers

Polyethylene Lumicene® mPE M 3410 EP

Technical data sheet
Metallocene Polyethylene BLOW MOULDING
Produced in Europe

Description

Lumicene® mPE M 3410 EP is a metallocene-based medium density polyethylene (MDPE) combining the features of conventional blow molding polyethylene with differentiated optical properties such as gloss and contact clarity.

Lumicene® mPE M 3410 EP is a pellet grade and contains antioxidants.

Characteristics

Property	Method	Unit	Typical value
Density	ISO 1183	kg/m ³	934
Melt Flow Rate (190°C/2.16 kg)	ISO 1133/D	g/10 min	0.9
ESCR AntaroX 100%	ASTM D 1693B	h	F ₅₀ > 1000
Notched Charpy Impact Resistance 23°C	ISO 179-1	kJ/m ²	80

(*) Data not intended for specification purposes

Handling and storage

Please refer to the safety data sheet (SDS) for handling and storage information. It is advisable to convert the product within one year after delivery provided storage conditions are used as given in the SDS of our product. SDS may be obtained from the website: www.polymers.totalenergies.com.

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